

Notice of References Cited	Application/Control No. 10/658,936	Applicant(s)/Patent Under Reexamination FASTOW, RICHARD M.	
	Examiner Dao H. Nguyen	Art Unit 2818	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,803,275	10-2004	Park et al.	438/257
	C	US-6,713,810	03-2004	Bhattacharyya, Arup	257/315
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NON-PATENT DOCUMENTS

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	U	http://www.semiconductorglossary.com/default.asp?SearchedField=Yes&SearchTerm=silicon+dioxide
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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